

2025 年度シラバス

科目分類/Subject Categories			
学部等/Faculty	/大学院工芸科学研究科（博士後期課程）： /Graduate School of Science and Technology (Doctoral Programs)	今年度開講/Availability	/有：/Available
学域等/Field	/＜その他＞：/＜Other＞	年次/Year	/1～3年次：/1st through 3rd Year
課程等/Program	/専攻共通科目：/Program-wide Subjects	学期/Semester	/春学期：/Spring term
分類/Category	/：/	曜日時限/Day & Period	/集中：/Intensive

科目情報/Course Information				
時間割番号 /Timetable Number	84109901			
科目番号 /Course Number	84160013			
単位数/Credits	2			
授業形態 /Course Type	講義：Lecture			
クラス/Class				
授業科目名 /Course Title	IGP 知的財産権特論：IGP Intellectual Property, Advanced			
担当教員名 / Instructor(s)	/国際センター長/(松浦 安紀子)/(藤島 孝太郎)：Director, International Center/0/0			
その他/Other	インターンシップ実施科目 Internship	国際科学技術コース提供科目 IGP	PBL 実施科目 Project Based Learning	DX 活用科目 ICT Usage in Learning
		○		○
	実務経験のある教員による科目 Practical Teacher	○	The lecturers have worked as examiners at the Japan Patent Office and are qualified as patent attorneys. They will offer the class on the intellectual property system.	
科目ナンバリング /Numbering Code	D_PS7231			

授業の目的・概要 Objectives and Outline of the Course	
日	
英	The purpose of this course is to provide basic knowledge of intellectual property rights. It is very important for researchers and engineers to properly manage and protect their research results as intellectual property rights. The lecture will focus on patents and copyrights, as well as trademarks and designs.

学習の到達目標 Learning Objectives	
日	Understand the importance and overview of the intellectual property system.
英	Understand the importance and overview of the intellectual property system.

学習目標の達成度の評価基準 / Fulfillment of Course Goals (JABEE 関連科目のみ)	
日	
英	

授業計画項目 Course Plan			
No.		項目 Topics	内容 Content
1	日		
	英	Overview of intellectual property rights	Lecture on overview of intellectual property rights, especially patent, utility model, design patent, trademark

2	日		
	英	Patent I	Lecture on patent system, patentable invention, procedures
3	日		
	英	Trademark I	Lecture on trademark system, registrable trademark, similarity of trademarks
4	日		
	英	Trademark II	Lecture on the rest of No. 3 and group project (group discussion)
5	日		
	英	Mini Test 1	Mini Test 1
6	日		
	英	Patent II	Lecture on the rest of No.2 and group project (group discussion)
7	日		
	英	Patent III	Lecture on patent topics important to universities
8	日		
	英	Unfair Competition and Trade Secret	Lecture on unfair competition prevention act and trade secret
9	日		
	英	Industrial Design	Lecture on industrial design system, registrable design
10	日		
	英	Mini Test 2	Test on topics No.6~No.9
11	日		
	英	Copyright I	Lecture on copyright act
12	日		
	英	Copyright II	Lecture on the rest of No. 11
13	日		
	英	Patent classification and search	Lecture on how to search the prior patent you are interested in
14	日		
	英	Recent topics of intellectual property rights II	Lecture on recent topics including the influence of AI on patent
15	日		
	英	Mini test 3	Test on topics No.11~No.14

履修条件 Prerequisite(s)

日	
英	

授業時間外学習（予習・復習等）

Required study time, Preparation and review

日	
英	<p>Lectures will be given in English.</p> <p>This course will be offered on August 27, 28, and 29, 2025.</p> <p>There will be group projects (group discussion) and three short tests.</p> <p>Grades will be based on the group projects (50%), mini-tests (50%).</p> <p>Please note that KIT requires 45 hours of study from students to award one credit, including both in-class instructions as well as study outside classes. Students are required to prepare for each class and complete the review after each class.</p>

教科書／参考書 Textbooks/Reference Books

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英	Presentation materials of this course will be uploaded on the website before the first day of the course.
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成績評価の方法及び基準 Grading Policy	
日	
英	Group projects (50%), Mini Test(50%)

留意事項等 Point to consider	
日	
英	<p>Dear Students;</p> <p>Welcome to Introduction of Intellectual Property Rights!</p> <p>This course will help you to acquire basic knowledge of various Intellectual Property Rights, such as patents and copyrights and to cope with the situation where you have some connection with Intellectual Property Rights in the future.</p> <p>We are looking forward to seeing you.</p>